

Absorption of highly reflective mirror coatings at 1550 nm

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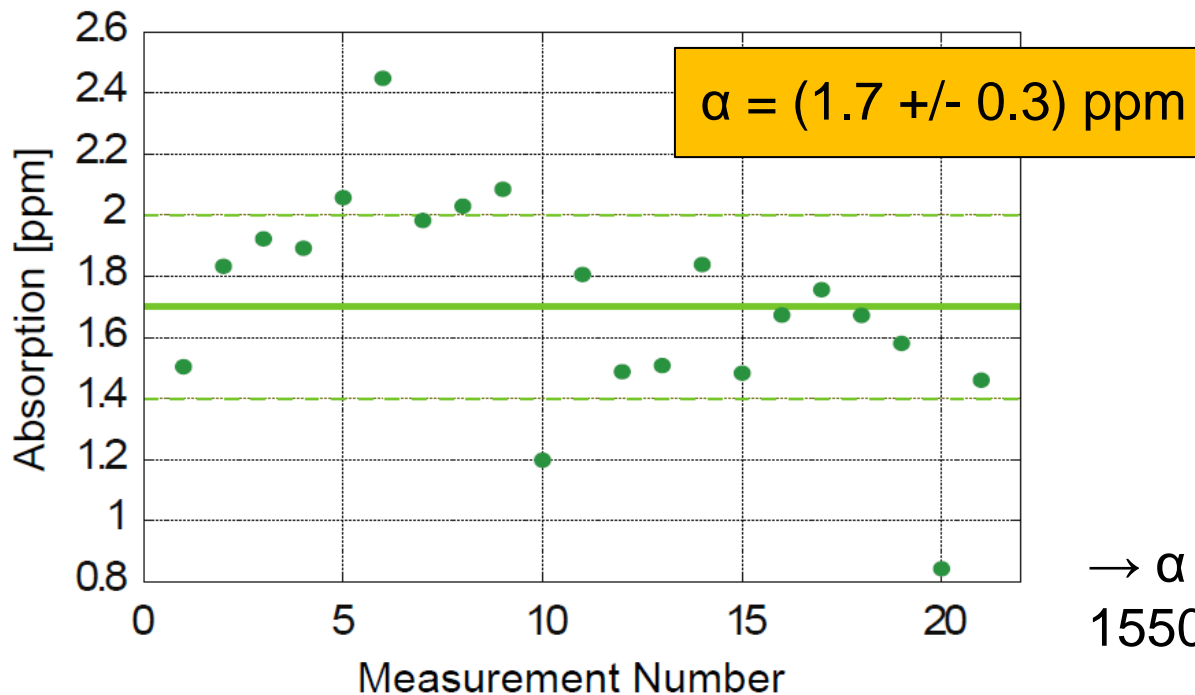




Optical absorption of $\text{SiO}_2/\text{Ta}_2\text{O}_5$ coatings at 1550 nm

We know: Optical absorption α of $\text{SiO}_2/\text{Ta}_2\text{O}_5$ @ 1064 nm is very low (< 1 ppm for LIGO and VIRGO optics)

What about 1550 nm?



Coating:

- ATF
- HR ($T \approx 530$ ppm)
- Good quality, but not optimized for low absorption in particular

→ α of $\text{SiO}_2/\text{Ta}_2\text{O}_5$ at 1550 nm very promising



Coating Thermal Noise of $\text{SiO}_2/\text{Ta}_2\text{O}_5$

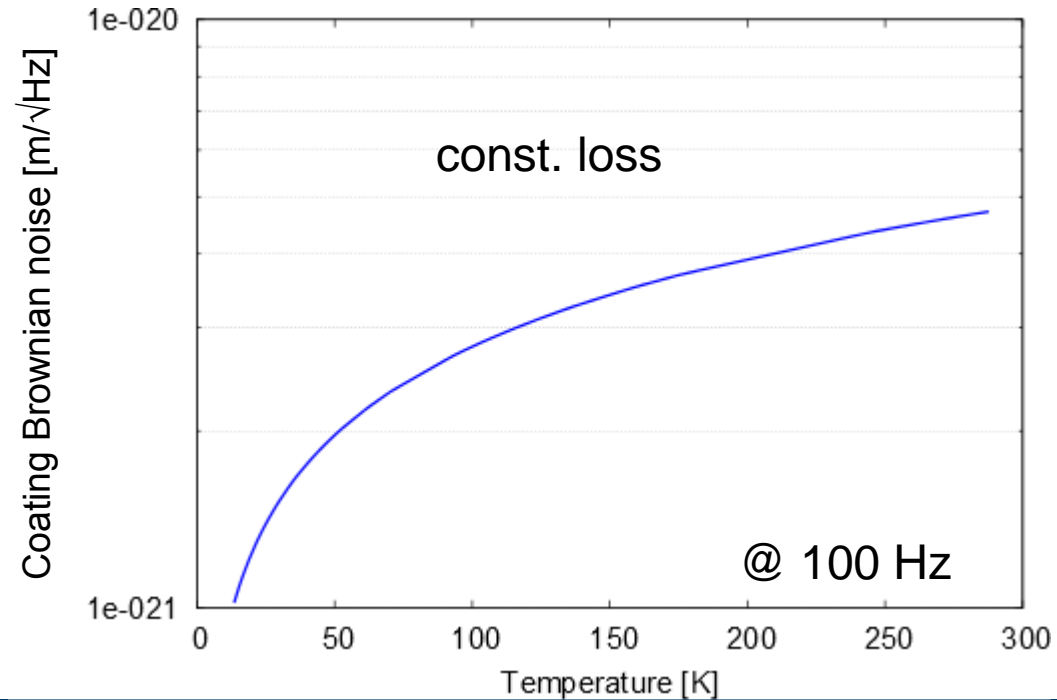
Temperature

Coating thickness

$$S_x(f, T) \approx \frac{2k_B T}{\pi^2 f} \frac{d}{w^2 Y} \phi \left(\frac{Y'}{Y} + \frac{Y}{Y'} \right)$$

Interferometer laser beam radius

Coating mechanical loss





Coating Thermal Noise of $\text{SiO}_2/\text{Ta}_2\text{O}_5$

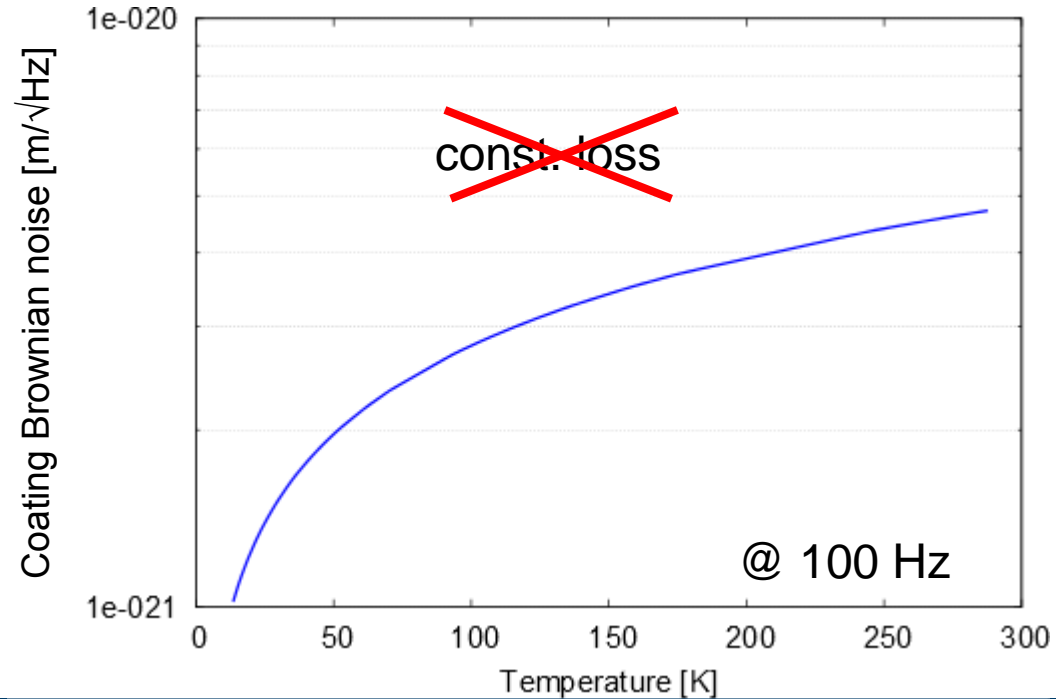
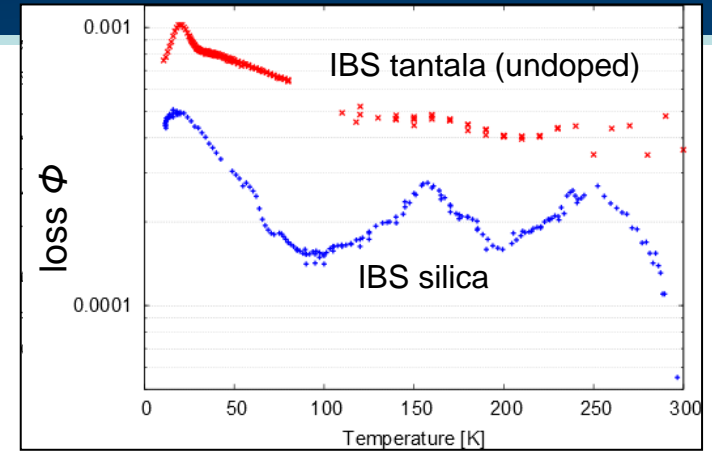
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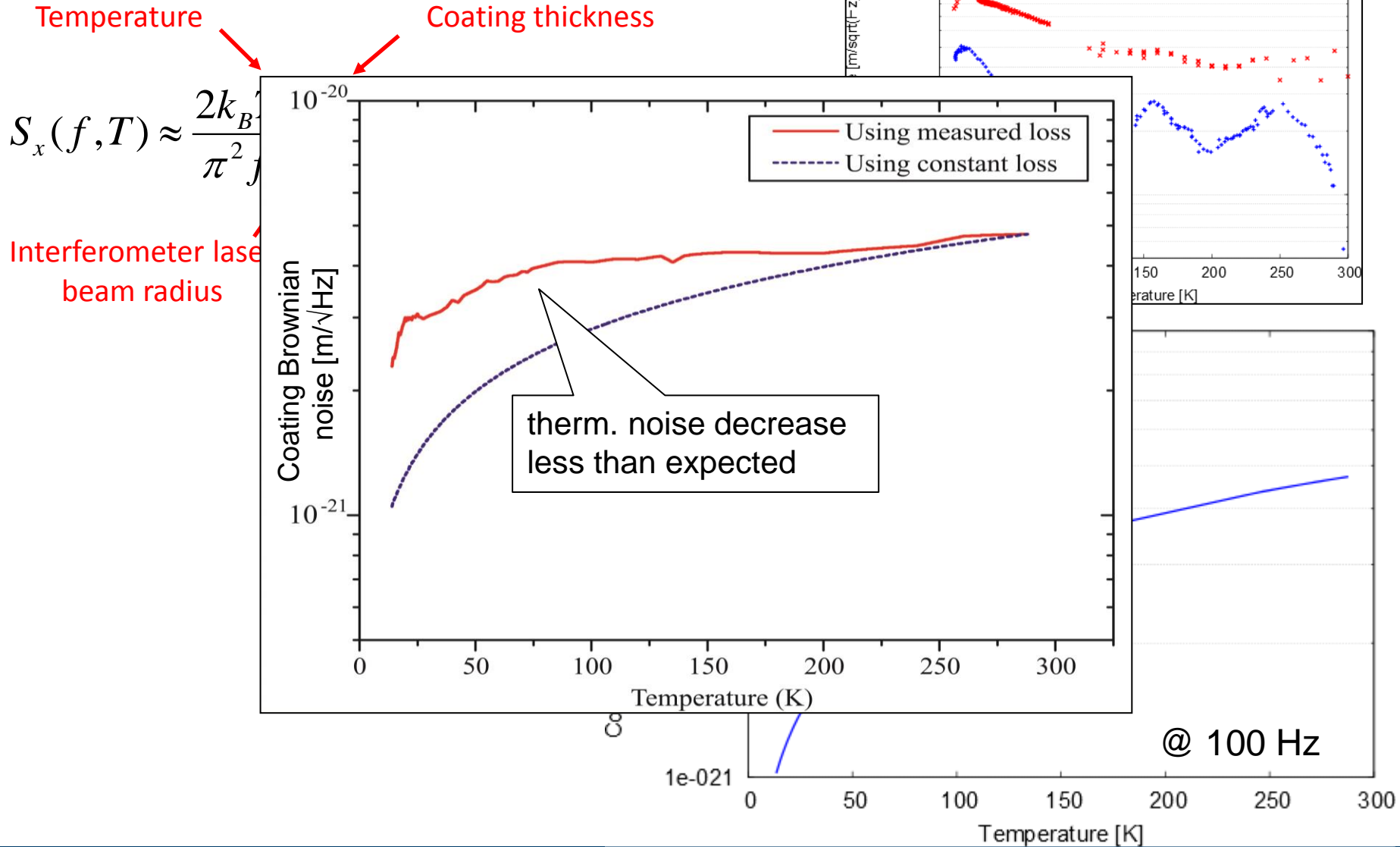
Interferometer laser beam radius

Coating mechanical loss





Coating Thermal Noise of $\text{SiO}_2/\text{Ta}_2\text{O}_5$

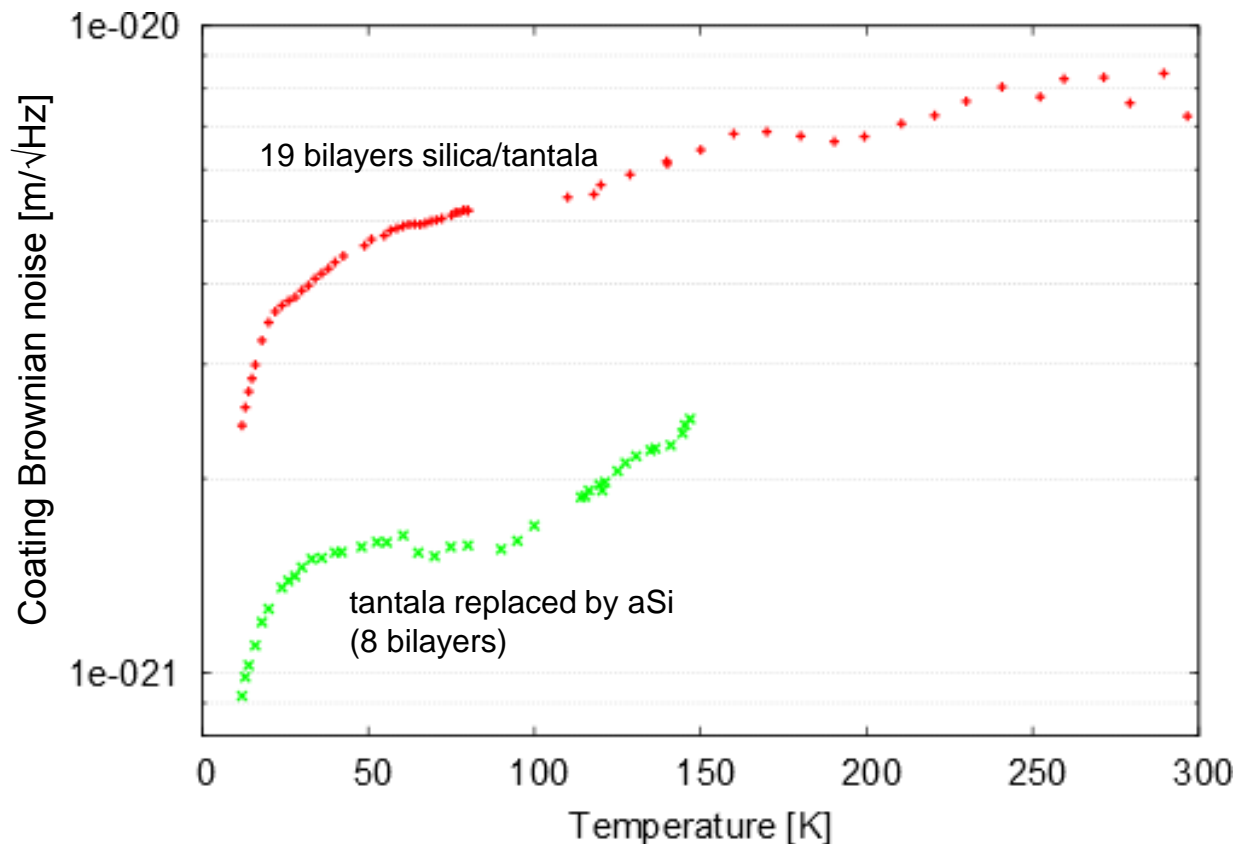




aSi for coatings? – Thermal noise ☺

aSi: significant lower loss than Ta_2O_5

Additionally: high refractive index ($n = 3.5$) reduces thickness of HR stack from about $8.7\mu\text{m}$ to $3.7\mu\text{m}$ (when replacing tantala by aSi)



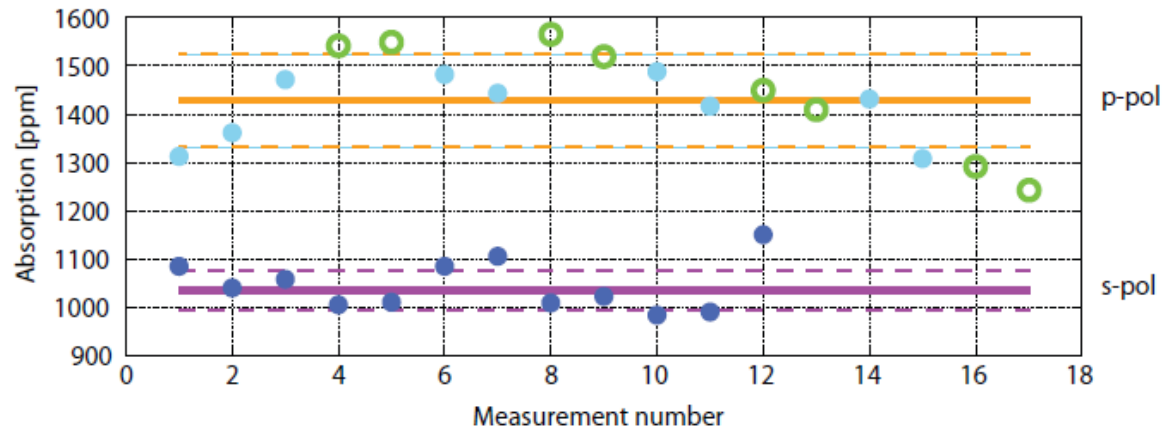


aSi for coatings? – Optical absorption at 1550 nm ☹️

Absorption for aSi/SiO₂ very high:

Absorption of *IBS* coatings extremely high (not measurable in cavity)

$\alpha \approx 1000$ ppm for *Ion Plating* HR stack @ AOI = 42 deg



Steinlechner, Khalaidovski and Schnabel, CQG (2014)

PCI measurement : $\alpha \approx 8000$ ppm for 500 nm single layer

→ ≈ 2700 ppm for a HR stack

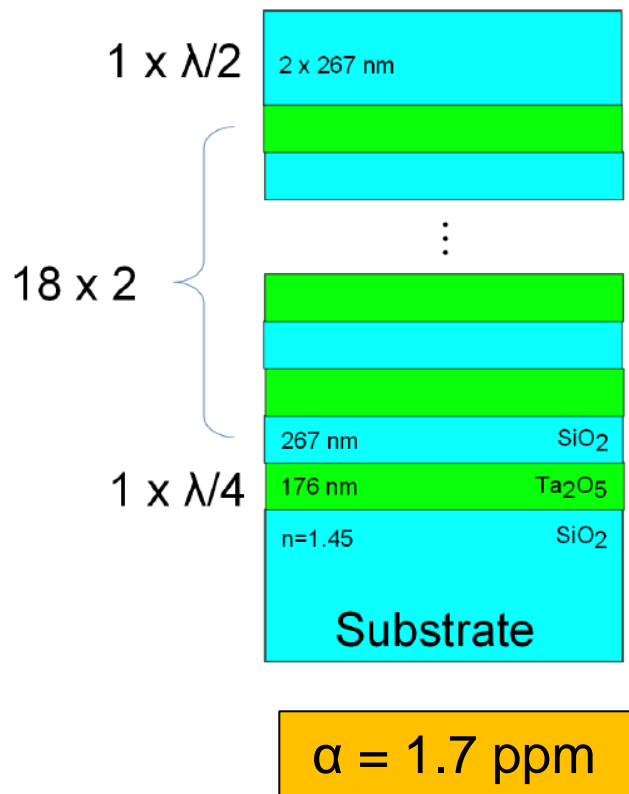
450°C heat treatment: α reduces by about 75%



Combining aSi with SiO₂/Ta₂O₅ - absorption

SiO₂/Ta₂O₅

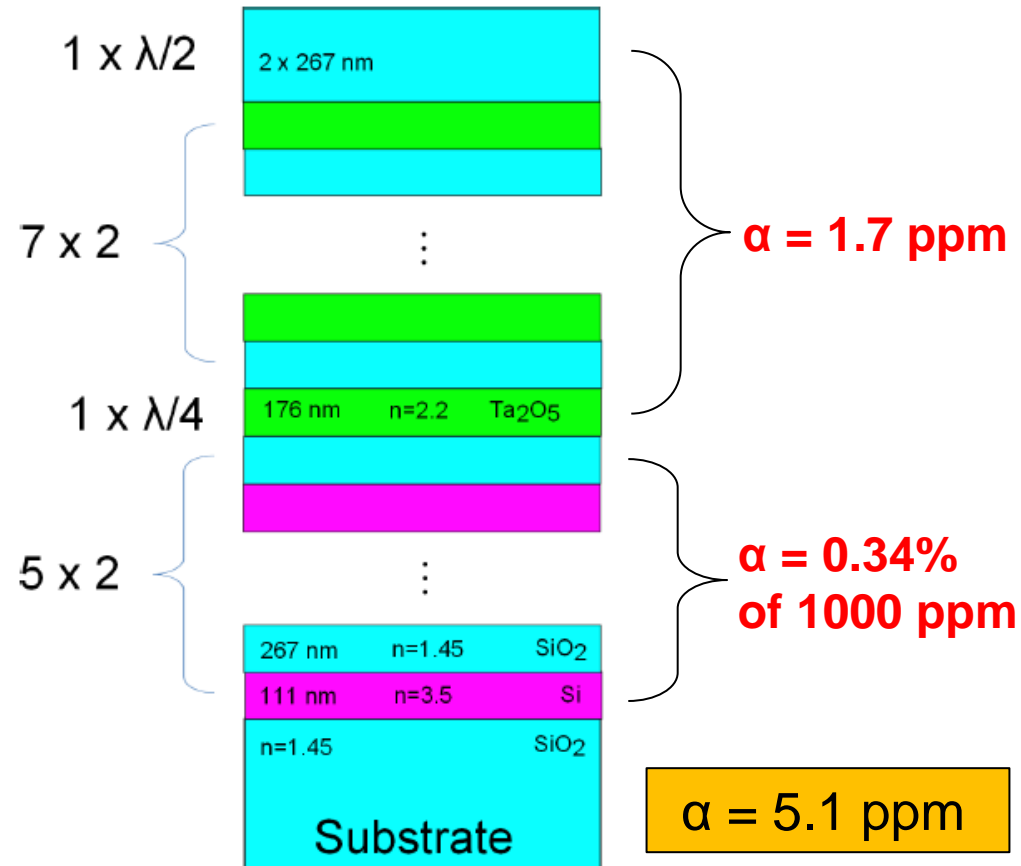
38 layers, T ≈ 0.5 ppm



vs.

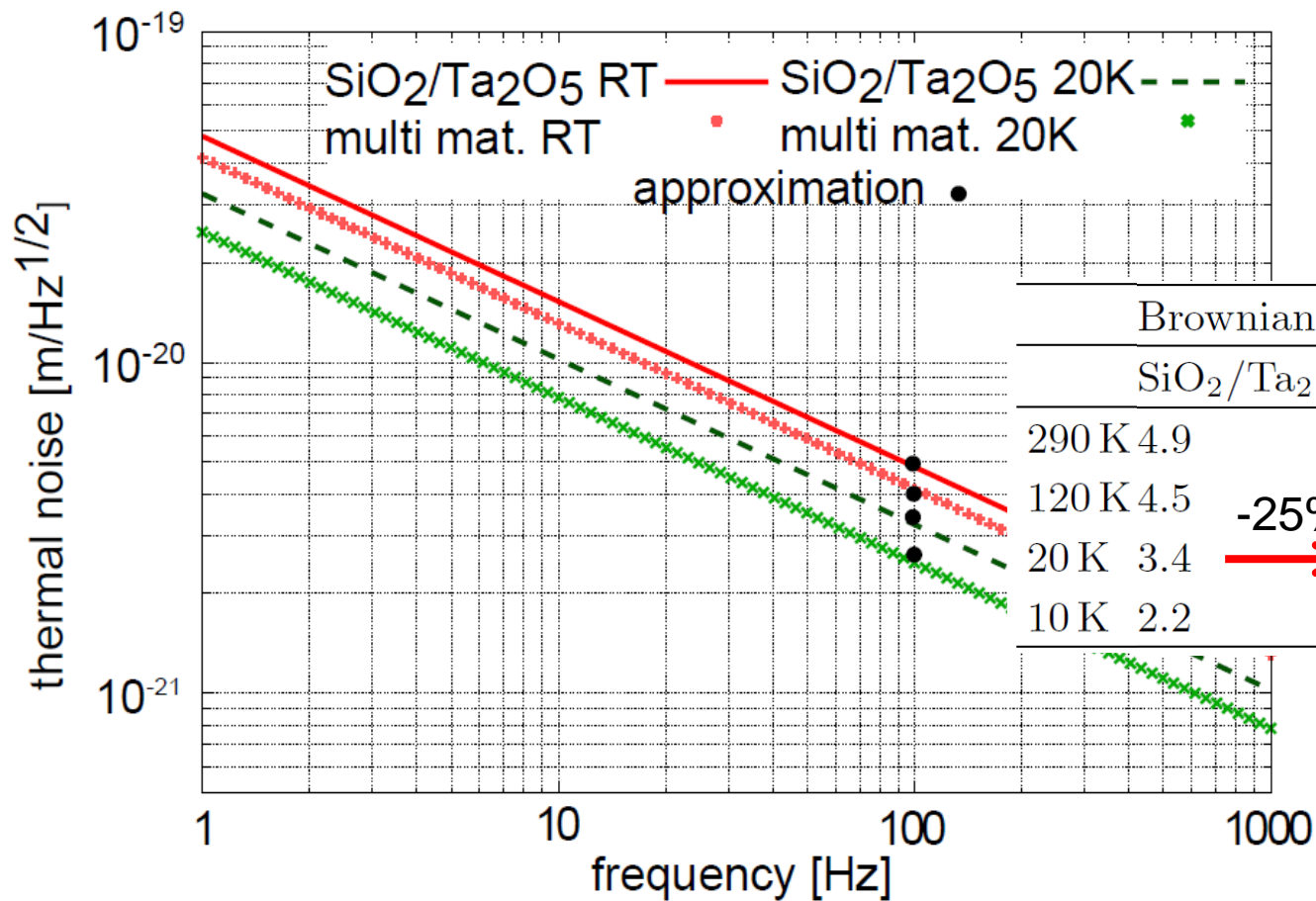
SiO₂/Ta₂O₅/aSi

26 layers, T ≈ 0.5 ppm





Combining aSi with SiO₂/Ta₂O₅ – thermal noise



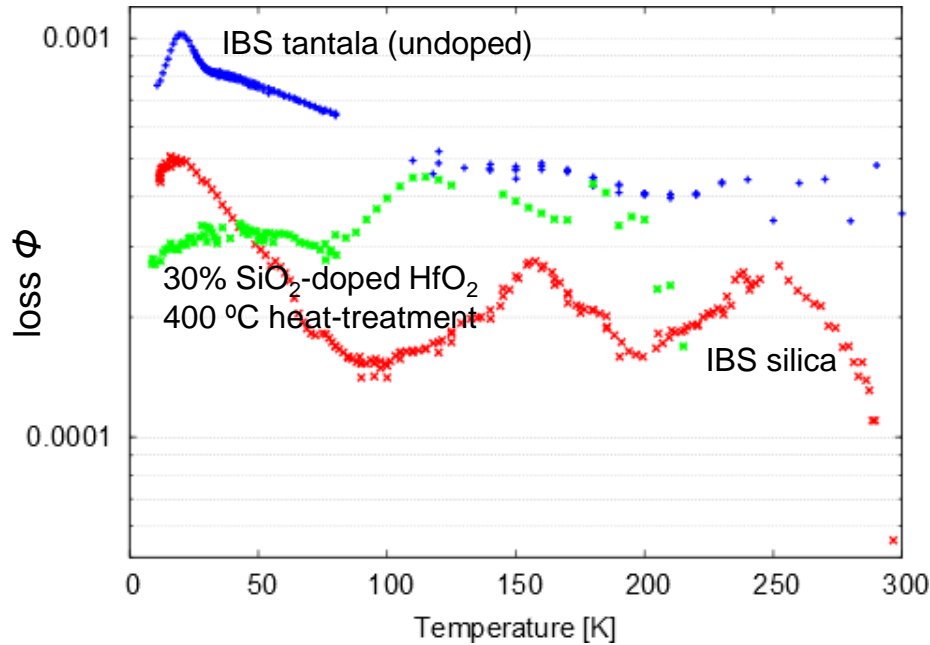
Brownian th. noise (100 Hz) × 10 ⁻²¹	
SiO ₂ /Ta ₂ O ₅ multi mat.	
290 K	4.9
120 K	4.5
20 K	3.4
10 K	2.2
	4.3
	3.5
	2.6
	1.7

-25%
→

Steinlechner et al. arXiv:1411.3150 [physics.optics]
 Yam, Gras, Evans arXiv:1411.3234 [physics.optics]



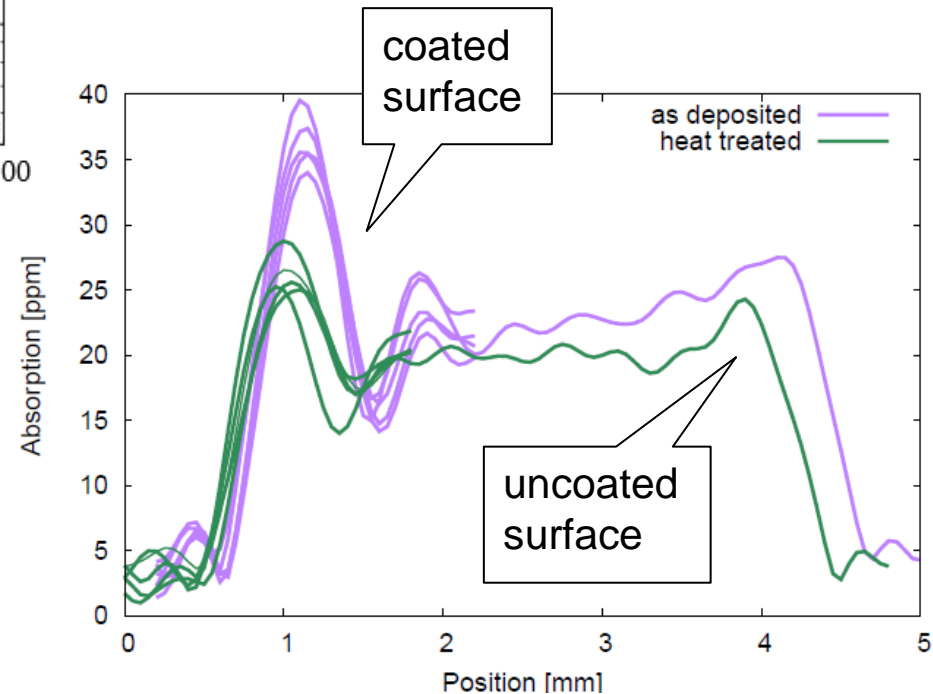
Silica doped Hafnia



- HR coating combined with silica:
~ 2 x 1000 nm → $\alpha \approx 20$ ppm
- HR coating combined with aSi:
~ 2 x 600 nm → $\alpha \approx 10$ ppm
(aSi absorption will dominate!)

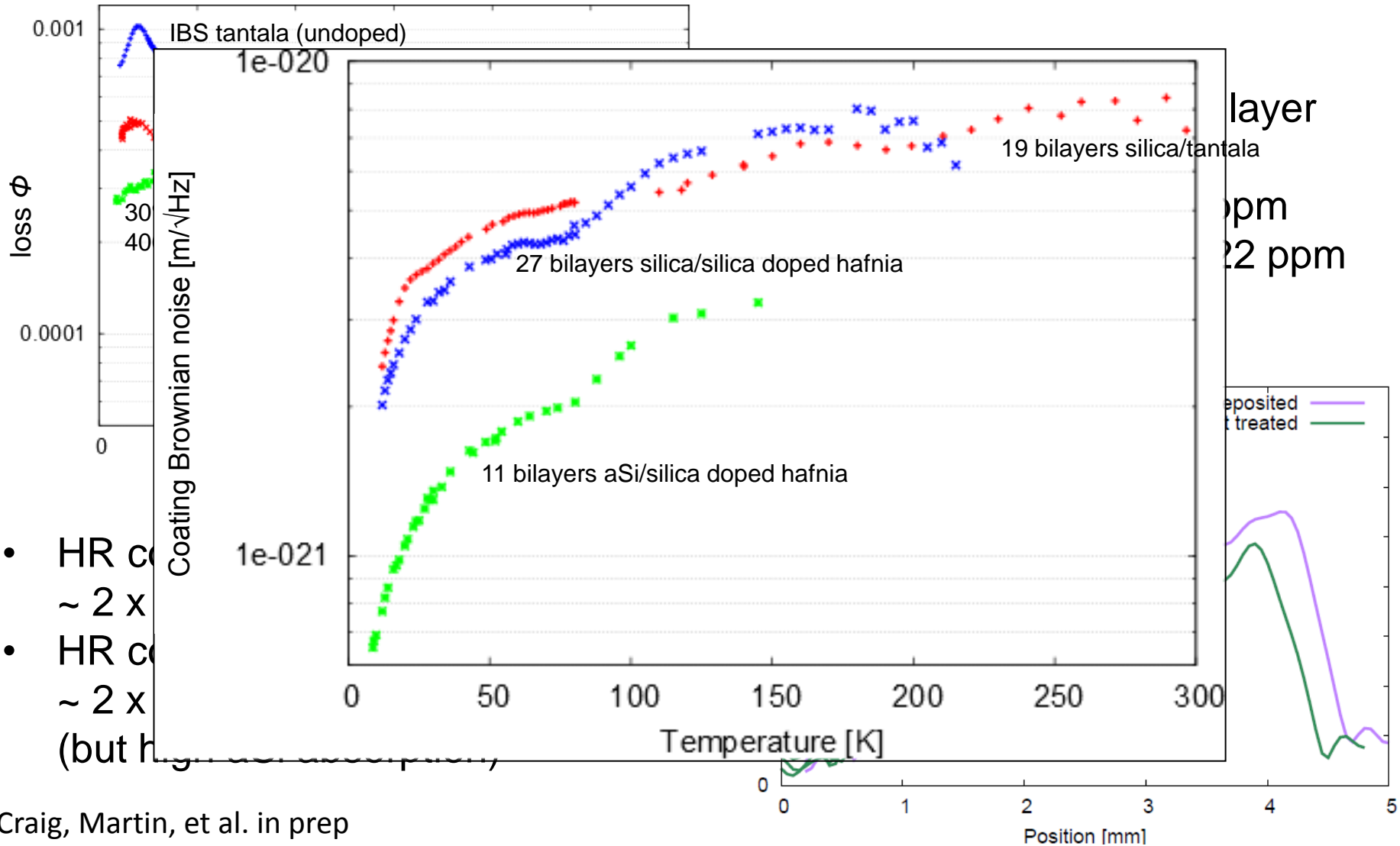
Craig et al. in prep

- SiO₂ doped HfO₂ (n=1.91):
Absorption of 500 nm single layer
- as deposited: ~36 ppm
 - 400 °C heat treated: ~26 ppm
 - uncoated back surface: ~22 ppm





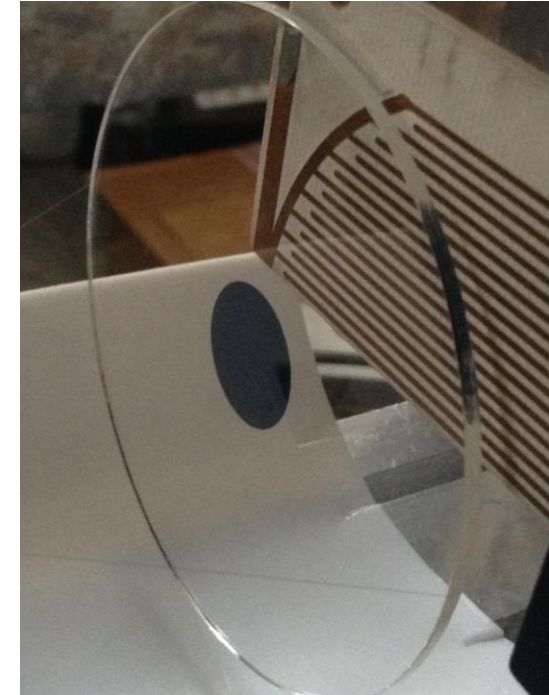
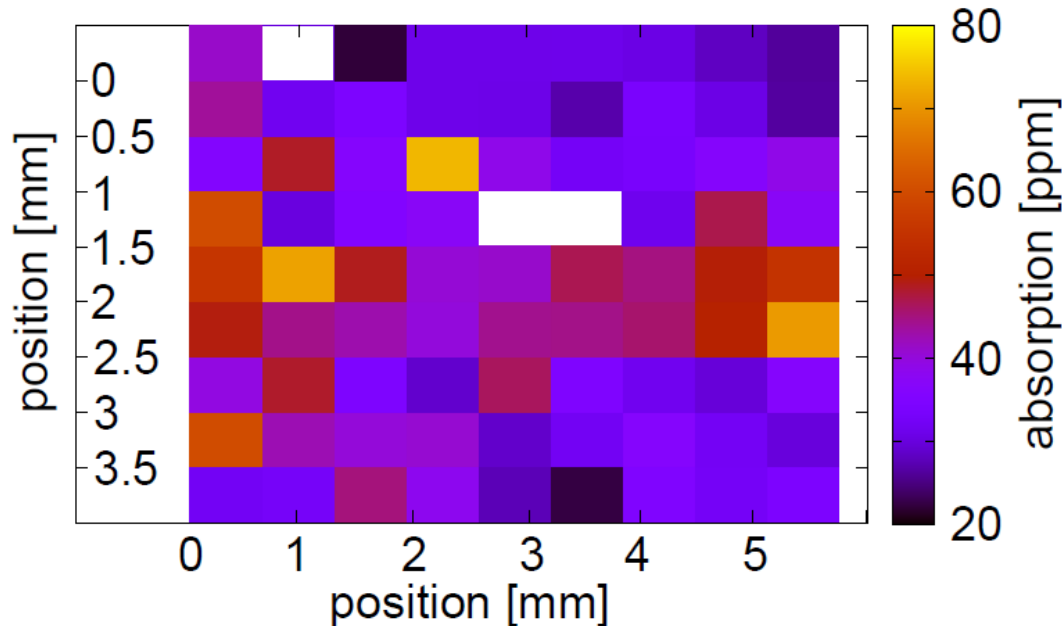
Silica doped Hafnia



- HR c
~ 2 x
- HR c
~ 2 x
(but h

Craig, Martin, et al. in prep

- $40.5 \times \text{GaAs}/\text{Al}_{0.92}\text{Ga}_{0.08}\text{As}$
- HR for 1064 nm
- Absorption measurement with PCI
- Measurement wavelength: 1530 nm ($T \approx 70\%$)



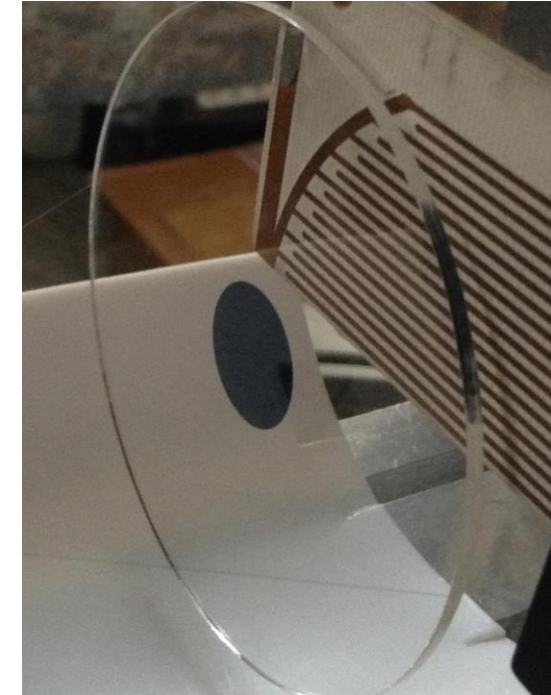
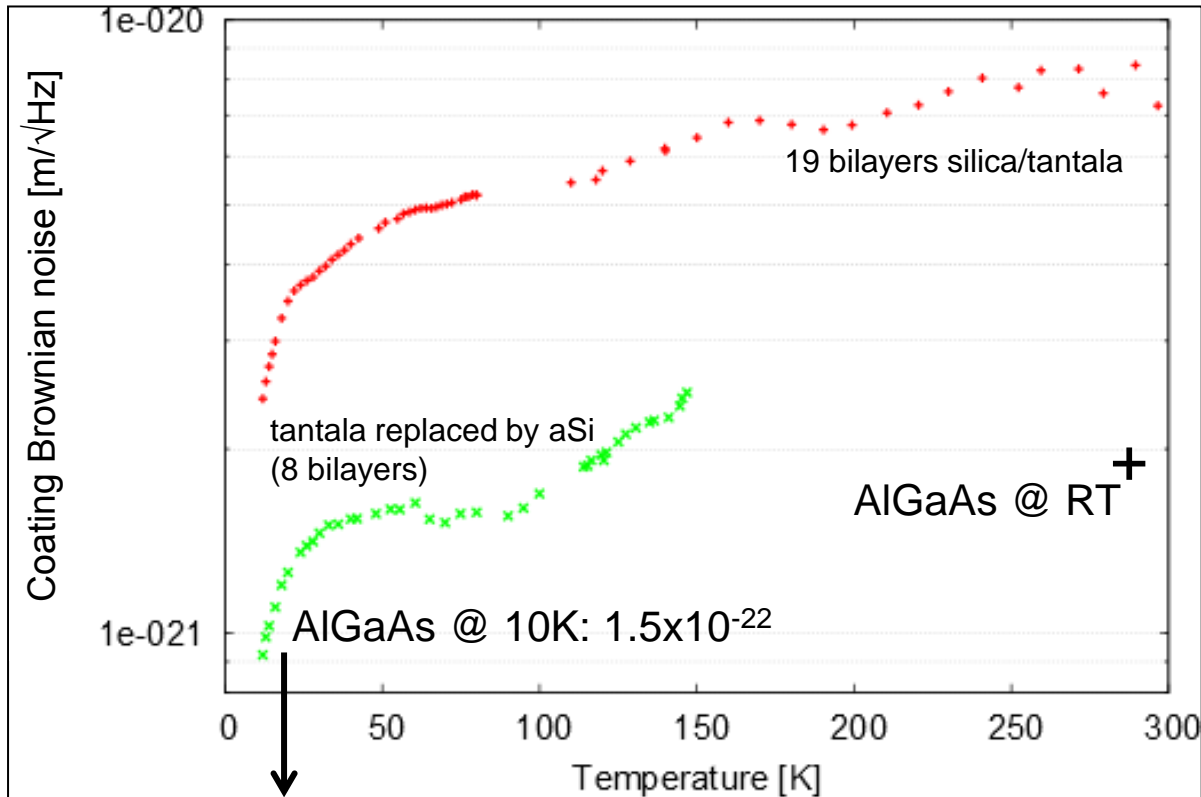
Mean value: $\alpha_{1530} = 30.2$ ppm
Scaled to HR: $\alpha_{\text{HR}} < 3.6$ ppm

Steinlechner, Martin, Cole et al. in prep. (DCC P1400226)



Crystalline AlGaAs Coating – Thermal Noise

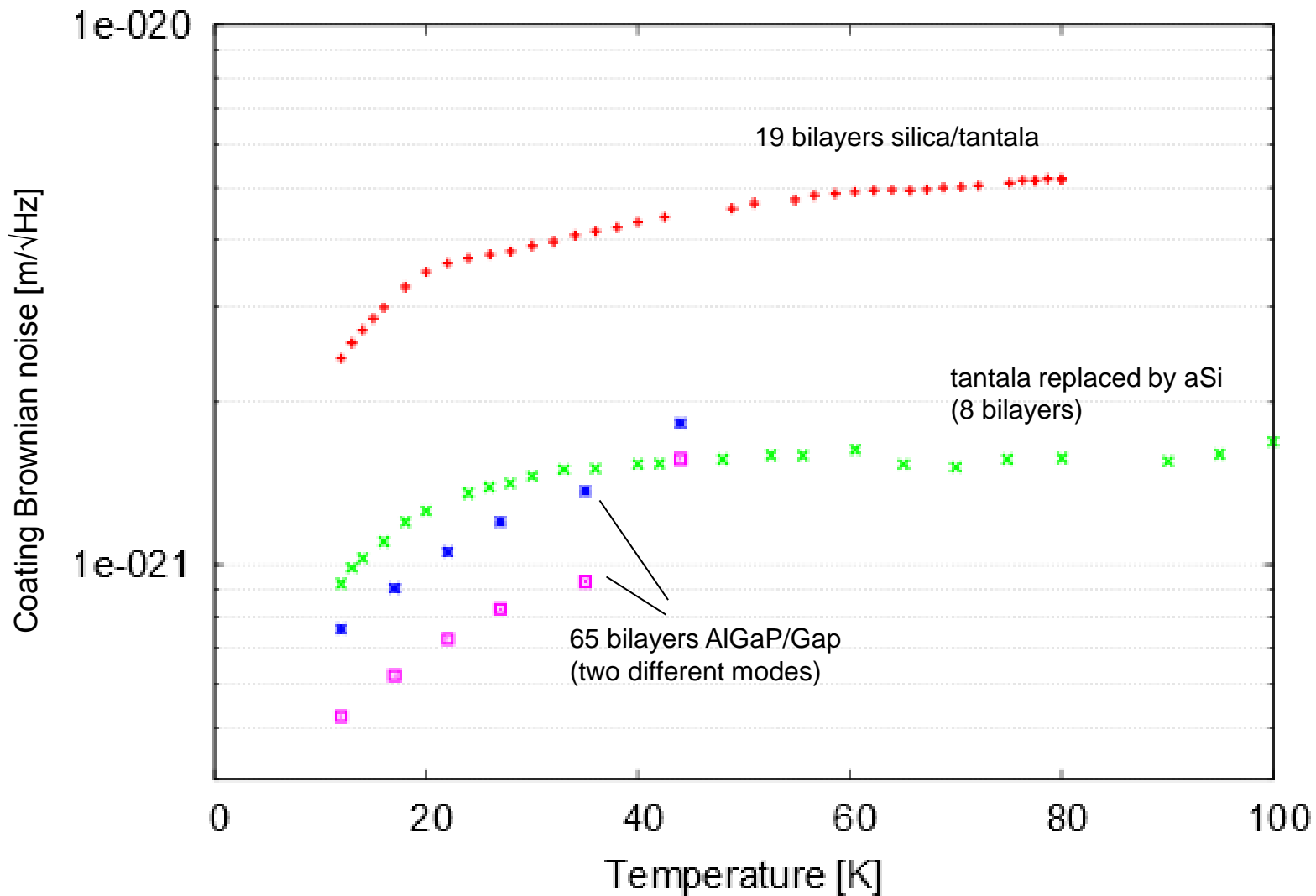
- $40.5 \times \text{GaAs}/\text{Al}_{0.92}\text{Ga}_{0.08}\text{As}^*$
- HR for 1064 nm



*Garrett D. Cole et al., Nature Photonics, 7, 644–650 (2013)

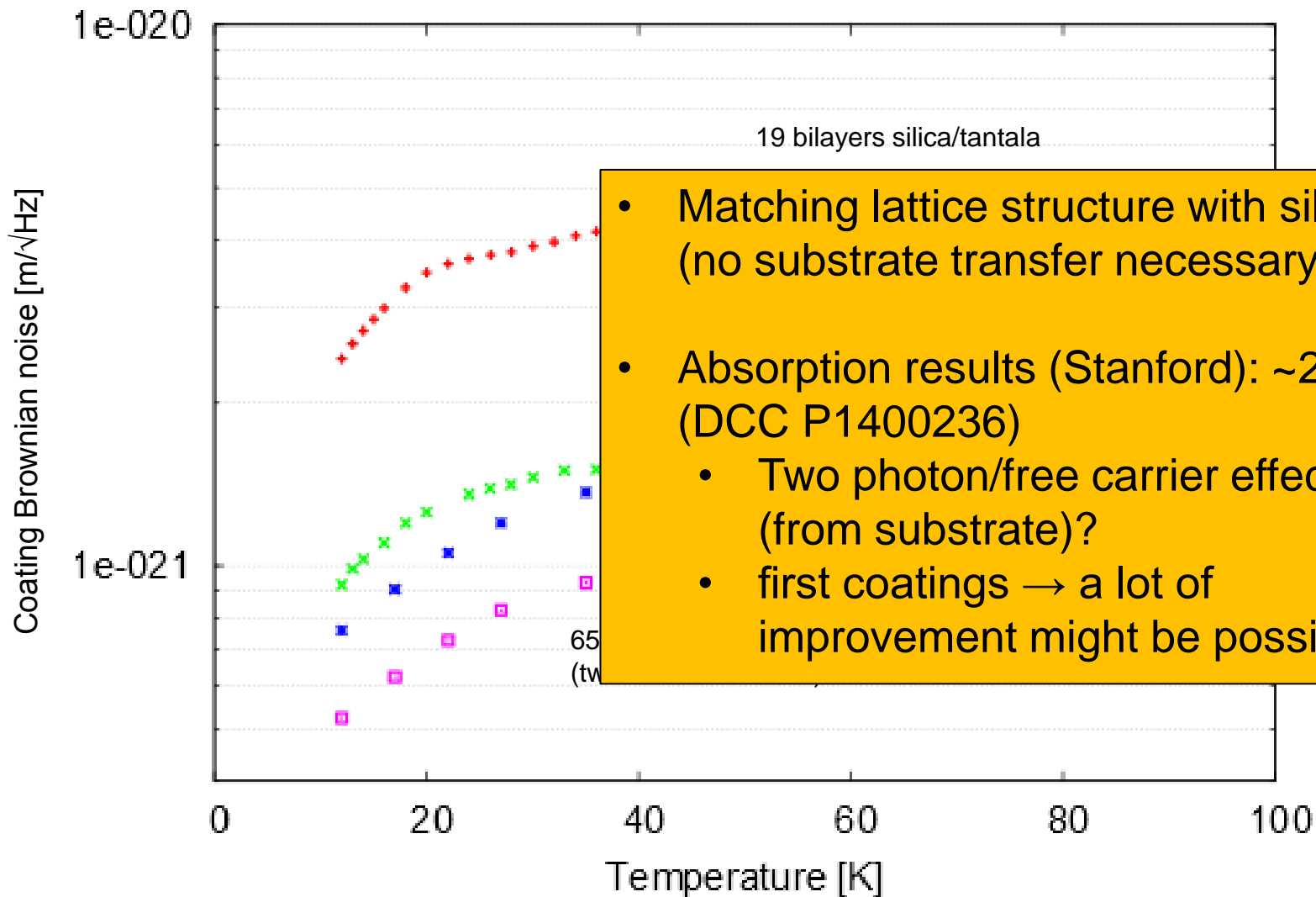


Crystalline AlGaP Coating – Thermal Noise





Crystalline AlGaP Coating – Thermal Noise





Summary

~ -50%

~ 1ppm (?)

	Therm. noise [m/VHz] @ 20 K	Absorption [ppm] @1550 nm
SiO ₂ /Ta ₂ O ₅	3.5x10 ⁻²¹	1.7
aSi/SiO ₂	1.7x10 ⁻²¹	1000
aSi/SiO ₂ /Ta ₂ O ₅	2.6x10 ⁻²¹	5
SiO ₂ -doped HfO ₂ /SiO ₂	2.7x10 ⁻²¹	20
SiO ₂ -doped HfO ₂ /aSi	1x10 ⁻²¹	1000
AlGaAs	1.5x10 ⁻²² (10 K)	4
AlGaP	1x10 ⁻²¹	2.3%



Summary

~ -50%

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SiO ₂ -doped HfO ₂ /SiO ₂	2.7x10 ⁻²¹	20
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AlGaAs	2x10 ⁻²² (10 K)	4
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Thanks for your attention!